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## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF:

**GROUP ART UNIT: 2815** 

JAMAL RAMDANI ET AL

SERIAL NO.: 09/766,046

**EXAMINER: BAUMEISTER** 

FILED: JANUARY 19, 2001

FOR: STRUCTURE AND METHOD FOR FABRICATING GAN DEVICES UTILIZING THE

FORMATION OF A COMPLIANT SUBSTRATE

## RESPONSE TO THE OFFICE COMMUNICATION DATED JANUARY 3, 2003

ASSISTANT COMMISSIONER FOR PATENTS WASHINGTON, D.C. 20231

SIR:

In response to the Official Action dated January 3, 2003, please amend the claims as follows.

## IN THE CLAIMS

Please amend Claim 7, 8, 10, 11, 13, 14, and 15 as follows.

--7. (Amended) The semiconductor structure of claim 6, wherein the template tayer is formed of material selected from the group comprising Ti-As, Sr-O-As, Sr-Ga-Q, Tayo-As, or Sr-Al-O.

8. (Amended) The semiconductor structure of claim 6, wherein the template layer comprises a Zintl-type phase material.

10. (Amended) The semiconductor structure of claim 6, wherein the template layer comprises a surfactant material.